## The 3rd International Symposium on Information Electronics Systems

Program at a Glance

July 13 - 14, 2009 at Sendai Excel Hotel Tokyu, Sendai, Japan

		Monday, July 13	
9:00-9:15		Opening Session	Chair: Eijiro Sumii
		Opening Remarks	Kunio Sawaya
		Welcome Address	Fumiyuki Adachi
9:15-10:30	Session 1	Wireless/Optical Communications and Networks (1)	Chair: Xiaohong Jiang
9:15-9:30	1-1	New Frontiers in Optical Communication: Ultrahigh-speed Transmission and	Masataka Nakazawa
		Coherent Transmission	
9:30-9:45	1-2	Design of Future All-Optical Routers	Susumu Horiguchi
9:45-10:00	1-3	Recent Advances in Frequency-Domain Equalization and Distributed Antenna	Fumiyuki Adachi
1000 1015	4.4	Network	o
10:00-10:15	1-4	Reflectarray Development for Improvement of Wireless Propagation Channel	Kunio Sawaya
10:15-10:30	1-5	A Fault-Tolerant Topology for Broadcasting in Ad-Hoc Networks	Nei Kato
10:30-11:00	<u> </u>	Break (O)	OL: T. 133 15 1
11:00-12:30	Session 2	Wireless/Optical Communications and Networks (2)	Chair: Toshihiko Hirooka
11:00-11:45	2-1(Invited)	The Progress of National 973 Project "Cognitive Radio Networks"	Zhang Ping
11:45-12:30	2-2(Invited)	Distributed Source Coding and its Research in China	Zhang Lin
12:30-13:45 13:45-15:15	Session 3	Lunch	Obeim Vulsie Iureus
13:45-14:30	3-1(Invited)	Intelligent Signal Processing and Multimedia Communications Technologies Haptic Collaborative Virtual Environments	<b>Chair: Yukio Iwaya</b> Hiromi T. Tanaka
10.70 14.00	o (mivited)	with Physics-Based Online -Remesh Volume Models	rmonn i. Tallana
14:30-14:45	3-2	Toward Highly Realistic Acoustic and Multi-Modal Information Systems	Yôiti Suzuki
14:45-15:00	3-3	Closed Form Expressions of the Balanced Realizations of Second-Order Filters	Masayuki Kawamata
15:00-15:15	3-4	High-Accuracy Machine Vision Technology Using Phase-Only Correlation	Takafumi Aoki
	<u> </u>	- From 3D Measurement to Biomedical Imaging -	
15:15-15:45		Break	
15:45-16:30	Session 4	Computing and Algorithm	Chair: Tachio Terauchi
15:45-16:00	4-1	Probabilistic Image Processing and Bayesian Networks	Kazuyuki Tanaka
16:00-16:15	4-2	Optimal Insertion of a Segment Highway in a City Metric	Takeshi Tokuyama
16:15-16:30	4-3	Overview of the TRecS Project	Naoki Kobayashi
16:30-17:45		Poster Session	Ball B
<u>17:45-19:45</u>		Banquet	Ball A
0.00 10.00	0	Tuesday, July 14	Oli '- Marri Oll Tala
9:00-10:30	Session 5	New Materials and Processing	Chair: Masao Sakuraba
9:00-9:45	5-1(Invited)	New Materials and Processing Group-IV Heteroepitaxial Films for Micro and Opto Electronic Devices	Joerg Schulze
9:00-9:45 9:45-10:00	5-1(Invited) 5-2	New Materials and Processing Group-IV Heteroepitaxial Films for Micro and Opto Electronic Devices Optoelectronic-Nanodevices Oriented Nanoscopic Plasma Control	Joerg Schulze Rikizo Hatakeyama
9:00-9:45	5-1(Invited)	New Materials and Processing Group-IV Heteroepitaxial Films for Micro and Opto Electronic Devices Optoelectronic-Nanodevices Oriented Nanoscopic Plasma Control Self-Alignment Process for the Fabrication of a Single Electron Transistor Using	Joerg Schulze
9:00-9:45 9:45-10:00 10:00-10:15	5-1(Invited) 5-2 5-3	New Materials and Processing Group-IV Heteroepitaxial Films for Micro and Opto Electronic Devices Optoelectronic-Nanodevices Oriented Nanoscopic Plasma Control Self-Alignment Process for the Fabrication of a Single Electron Transistor Using Anodization of an Aluminum Microelectrode	Joerg Schulze Rikizo Hatakeyama Michio Niwano
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